

Patent Application Serial No	09/905,320
Patent Application Serial No	6172
Confirmation NoFiling Date	duly 10, 200 ·
Inventor	Cem Basceri et al.
Assignee	1762
Group Art Unit	Eric R Fuller
Examiner	MI22-1657
Attorney Docket No.	021567
Customer No. Title: Chemical Vapor Deposition Methods of Forming Comprising Dielectric Layers, Including Such Concentration of Barium and Strontium Within	Barium Strontium Titanate Layers Having a Varied

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Copies of the cited art are included. No admission is made regarding whether all the submitted references are prior art.

Respectfully submitted,

Dated: 9-25-03

Reg. No. 32,268

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. MI22-1657

SERIAL NO. 09/905,320

APPLICANT: Cem Basceri et al.

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U.S. PATEN	IT DOC	UMENTS										
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